
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PATENTIn re application of: Ricci *et al.*Attorney Docket No.:
LAM1P118/P0539

Application No.: 09/408,921

Examiner: A. Powell

Filed: September, 30, 1999

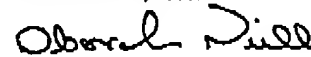
Group: 1763

Title: PRETREATED GAS DISTRIBUTION PLATE

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NWCERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail to: Commissioner for Patents, Washington, DC 20231 on November 6, 2001.

Signed:



Deborah Neill

AMENDMENT B

Commissioner for Patents
Box Non-Fee Amendment
Washington, D.C. 20231

Sir:

This is in response to the Office Action mailed August 6, 2001.
Reconsideration of the captioned application is respectfully requested.

IN THE CLAIMS:

Please AMEND claims 1, 5, 7, 8, 12-15 and 38-39 as follows:

1. (Twice Amended) A gas distribution plate for use in a semiconductor fabrication apparatus including a semiconductor processing chamber, the gas distribution plate comprising:

a plurality of holes for passing process gases to the semiconductor processing chamber, and

a portion exposed to the process chemistry used in the semiconductor fabrication apparatus, wherein the portion of the gas distribution plate has substantially no micro-defects about 50 micrometers or greater, after machining, that may lead to contamination of a wafer located within said semiconductor processing chamber.

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